



AF/EPW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:	§	
Robert P. Meagley et al.	§	Art Unit: 1752
	§	
Serial No.: 10/688,521	§	Examiner: Amanda C. Walke
	§	
Filed: October 17, 2003	§	Docket: ITL1026US
	§	P16713
For: Reducing Photoresist Line Edge	§	
Roughness Using Chemically-	§	Assignee: Intel Corporation
Assisted Reflow	§	

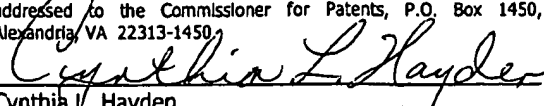
Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**REPLY TO FINAL REJECTION**

Sir:

In response to the final rejection mailed August 26, 2005, reconsideration is requested in view of the following remarks.

Okay  
to Enter  
ACW 10/6/05

Date of Deposit: September 19, 2005  
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.  
  
Cynthia L. Hayden